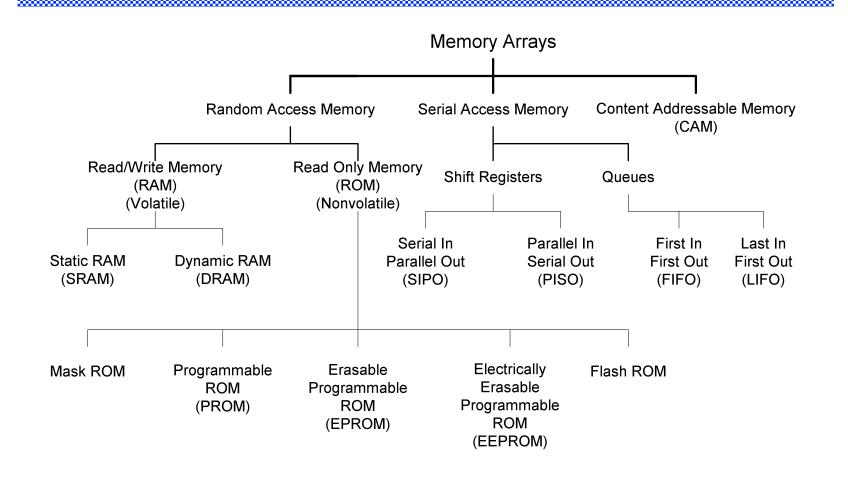


Lecture 19: SRAM

Outline

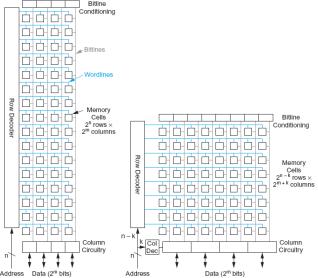
- Memory Arrays
- SRAM Architecture
 - SRAM Cell
 - Decoders
 - Column Circuitry

Memory Arrays



Array Architecture

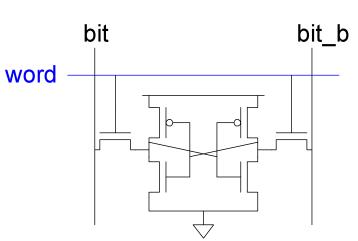
- □ 2ⁿ words of 2^m bits each
- \Box If n >> m, fold by 2^k into fewer *rows* of more *columns*



- ☐ Good regularity easy to design
- Very high density if good cells are used

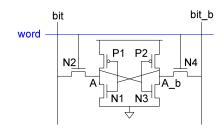
6T SRAM Cell

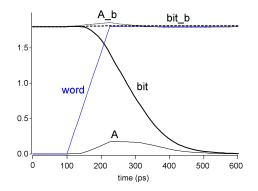
- ☐ Cell size accounts for most of array size
 - Reduce cell size at expense of complexity
- 6T SRAM Cell
 - Used in most commercial chips
 - Data stored in cross-coupled inverters
- ☐ Read:
 - Precharge bit, bit_b
 - Raise wordline
- ☐ Write:
 - Drive data onto bit, bit b
 - Raise wordline



SRAM Read

- Precharge both bitlines high
- ☐ Then turn on wordline
- One of the two bitlines will be pulled down by the cell
- \Box Ex: A = 0, A_b = 1
 - bit discharges, bit_b stays high
 - But A bumps up slightly
- ☐ Read stability
 - A must not flip
 - N1 >> N2



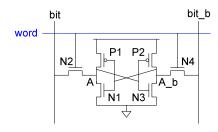


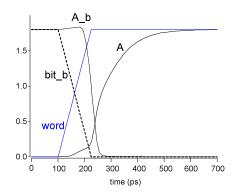
SRAM Write

- ☐ Drive one bitline high, the other low
- ☐ Then turn on wordline
- ☐ Bitlines overpower cell with new value
- \Box Ex: A = 0, A_b = 1, bit = 1, bit_b = 0
 - Force A_b low, then A rises high
- □ Writability

19: SRAM

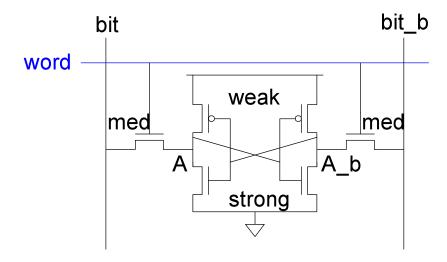
- Must overpower feedback inverter
- N2 >> P1





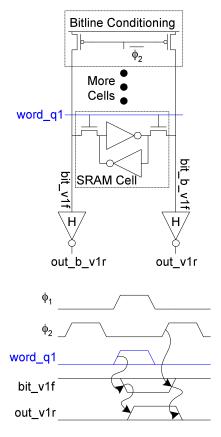
SRAM Sizing

- High bitlines must not overpower inverters during reads
- But low bitlines must write new value into cell

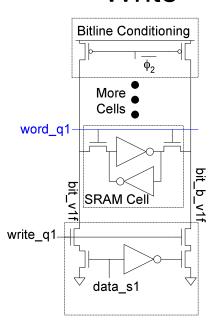


SRAM Column Example

Read

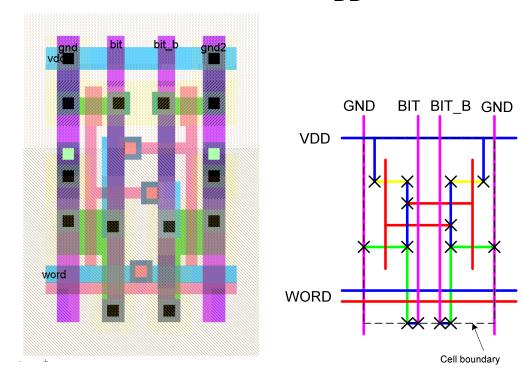


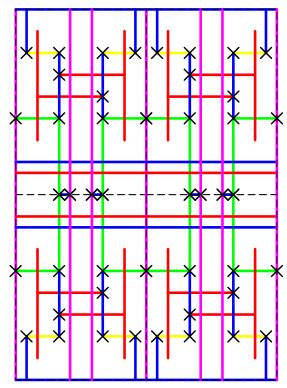
Write



SRAM Layout

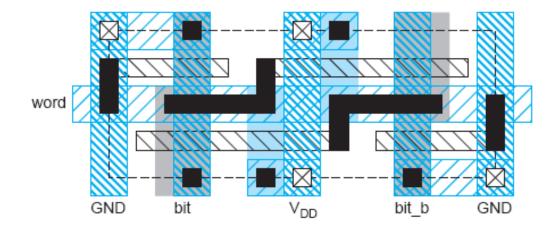
- \Box Cell size is critical: 26 x 45 λ (even smaller in industry)
- ☐ Tile cells sharing V_{DD}, GND, bitline contacts





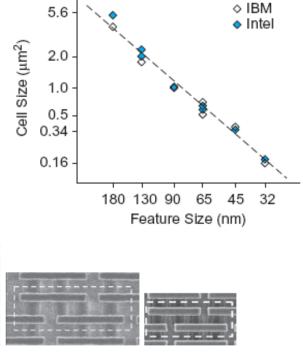
Thin Cell

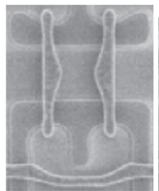
- □ In nanometer CMOS
 - Avoid bends in polysilicon and diffusion
 - Orient all transistors in one direction
- ☐ Lithographically friendly or thin cell layout fixes this
 - Also reduces length and capacitance of bitlines

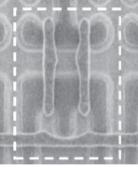


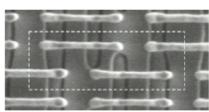
Commercial SRAMs

- ☐ Five generations of Intel SRAM cell micrographs
 - Transition to thin cell at 65 nm
 - Steady scaling of cell area









1 µm

130 nm [Tyagi00]

90 nm [Thompson02]

65 nm [Bai04]

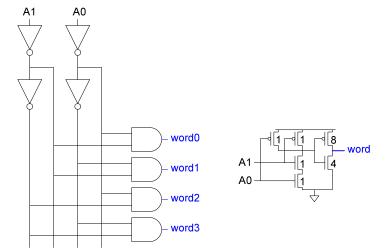
45 nm [Mistry07]

32 nm [Natarajan08]

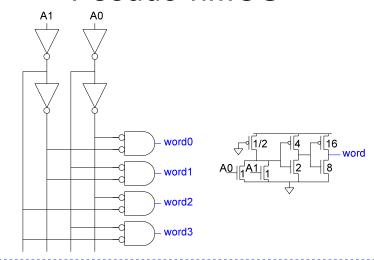
Decoders

- □ n:2ⁿ decoder consists of 2ⁿ n-input AND gates
 - One needed for each row of memory
 - Build AND from NAND or NOR gates

Static CMOS

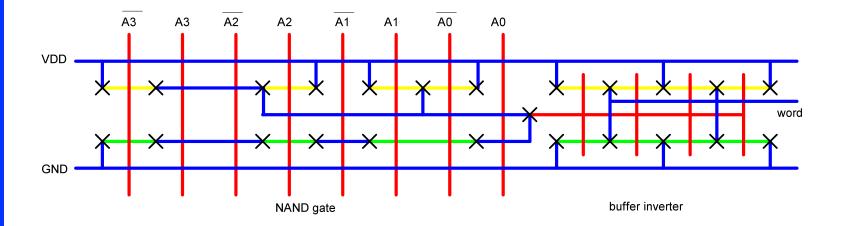


Pseudo-nMOS



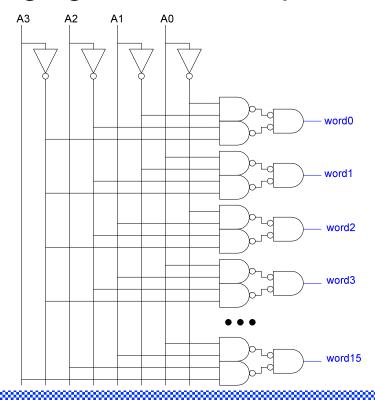
Decoder Layout

- □ Decoders must be pitch-matched to SRAM cell
 - Requires very skinny gates



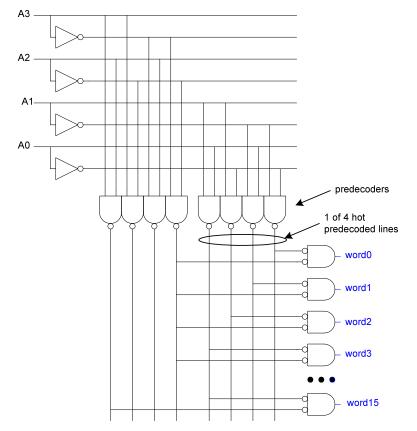
Large Decoders

- ☐ For n > 4, NAND gates become slow
 - Break large gates into multiple smaller gates



Predecoding

- Many of these gates are redundant
 - Factor out common gates into predecoder
 - Saves area
 - Same path effort

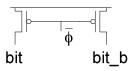


Column Circuitry

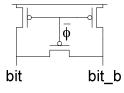
- Some circuitry is required for each column
 - Bitline conditioning
 - Sense amplifiers
 - Column multiplexing

Bitline Conditioning

☐ Precharge bitlines high before reads



□ Equalize bitlines to minimize voltage difference when using sense amplifiers

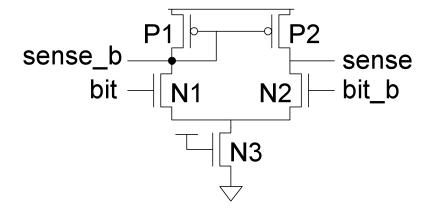


Sense Amplifiers

- □ Bitlines have many cells attached
 - Ex: 32-kbit SRAM has 128 rows x 256 cols
 - 128 cells on each bitline
- \Box $t_{pd} \propto (C/I) \Delta V$
 - Even with shared diffusion contacts, 64C of diffusion capacitance (big C)
 - Discharged slowly through small transistors (small I)
- \Box Sense amplifiers are triggered on small voltage swing (reduce ΔV)

Differential Pair Amp

- Differential pair requires no clock
- But always dissipates static power



20

Clocked Sense Amp

- Clocked sense amp saves power
- Requires sense_clk after enough bitline swing
- ☐ Isolation transistors cut off large bitline capacitance

